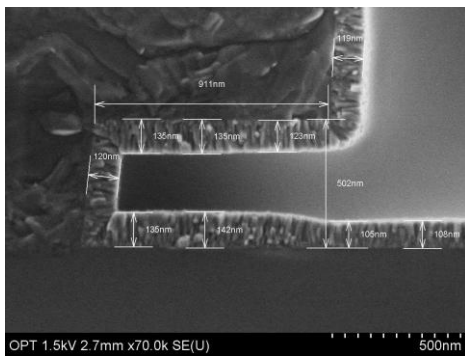
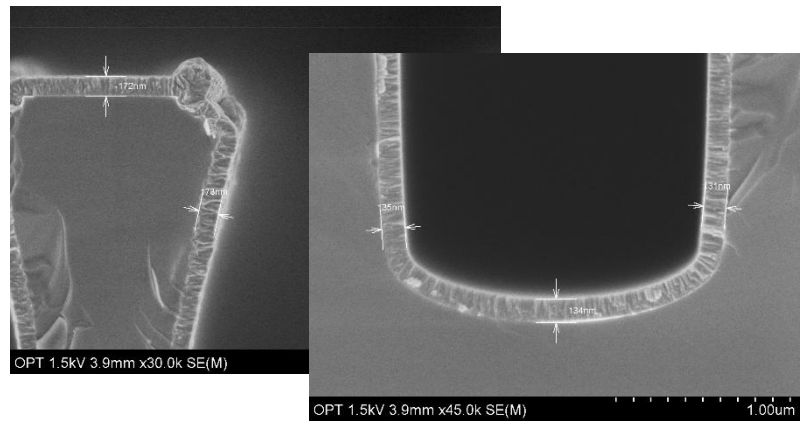


Images:

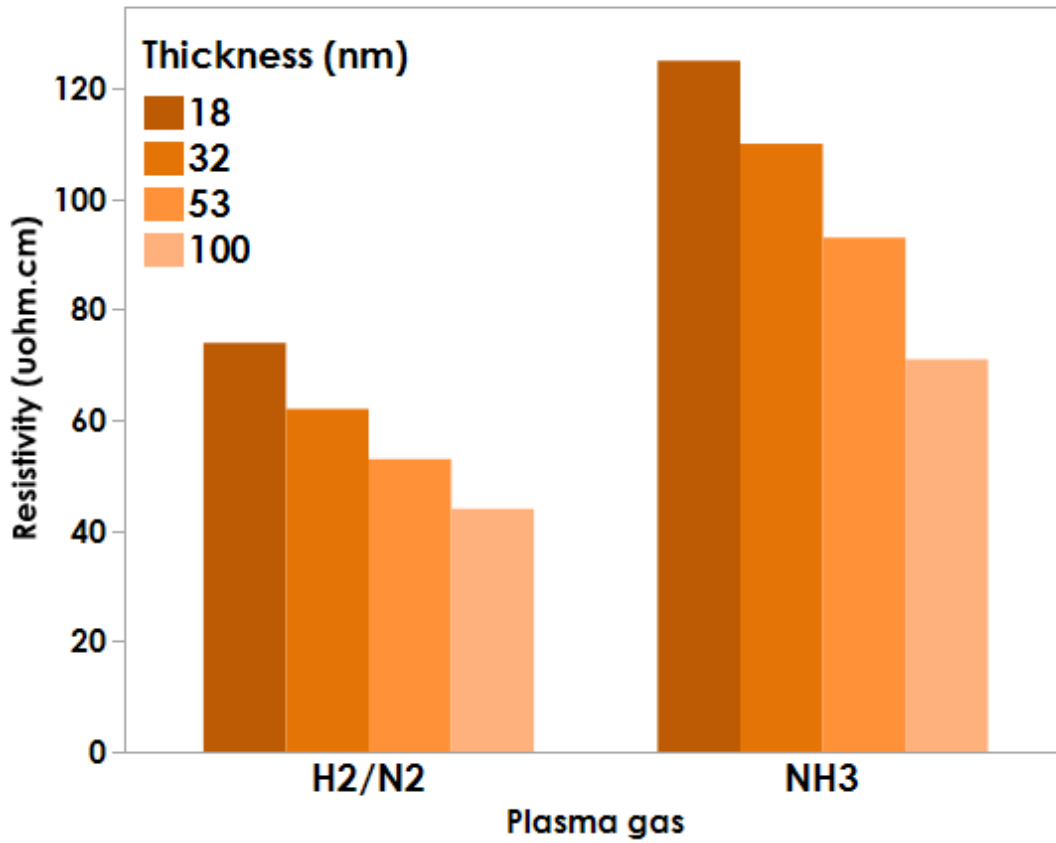


TiN conformality in 2:1 LHAR



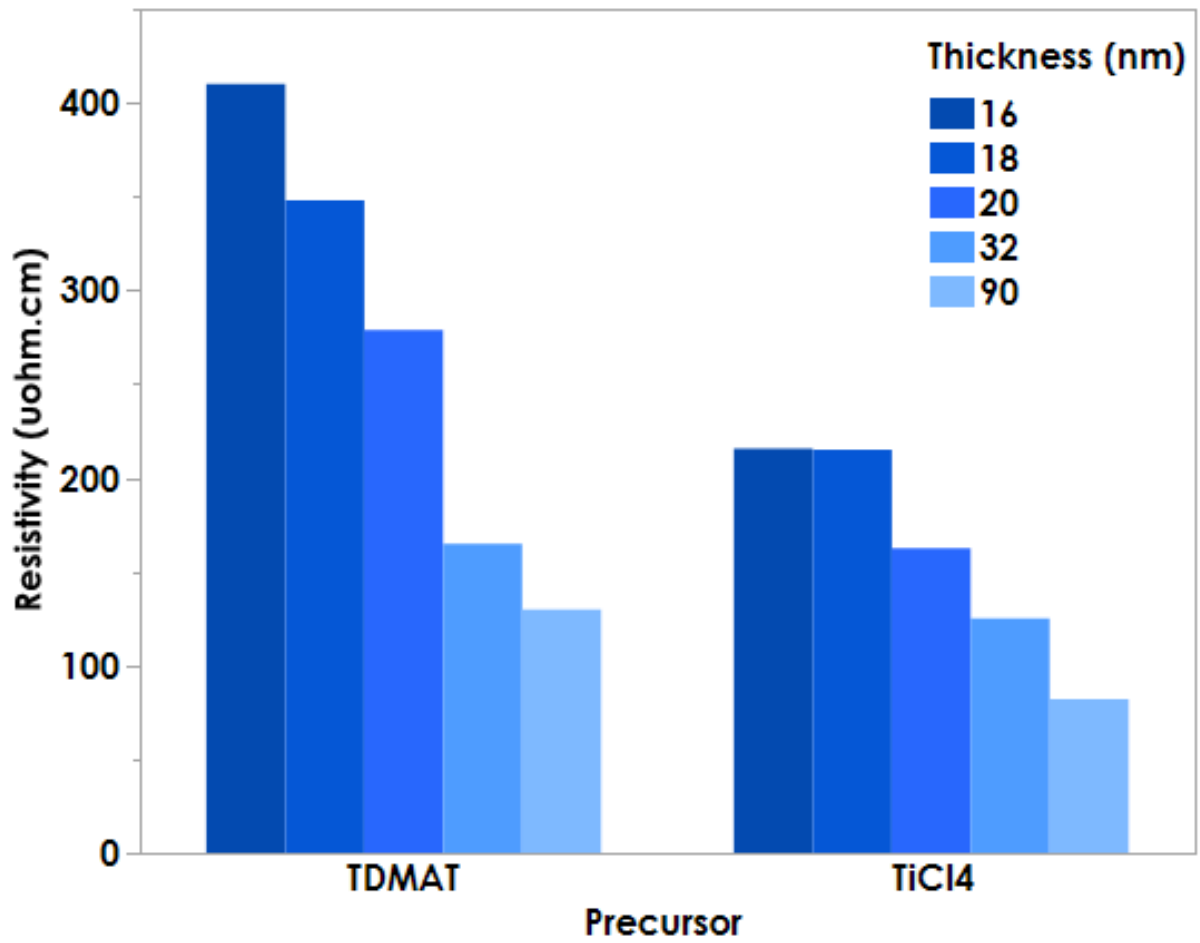
TiN conformality in 12:1 AR

Resistivity Comparison across Plasma Gas Mix

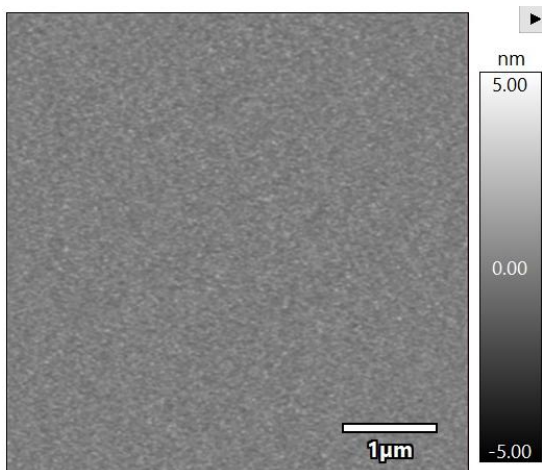


H₂/N₂ plasma gas mix yields lower resistivity

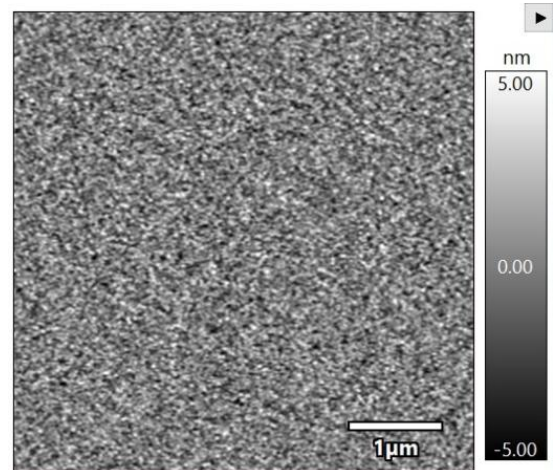
Resistivity Comparison vs. Precursor



TiCl₄ yields lower resistivity than TDMAT



Roughness of TDMAT TiN Films is ~276 pm



Roughness of TiCl₄ TiN Films is ~1.5 nm